

INFORMATION DISCLOSURE STATEMENT BY APPLICANT Sheet 1 of 1 		Application Number: 10/646,460 Filing Date: August 22, 2003 First Named Inventor: Kenneth COLLINS, et al. Group Art Unit: 1763 Examiner Name: Maureen G. Arancibia Attorney Docket Number: 006915 P09					
U. S. PATENT DOCUMENTS							
Examiner Initials	Document Number	Publication Date	Name of Patentee or Applicant of Cited Document		Class	Subclass	Filing Date
MPJ	US-6,395,150 B1 US-6,413,321 B1 US 2003/0013260 A1 US 2003/0085205 A1	05-28-2002	CAN CLEEMPUT ET AL. KIM ET AL. GOSSMAN ET AL. LAI ET AL.		204	192.37	04-01-1998
MPJ		07-02-2002			118	725	12-07-2000
MPJ		01-16-2003			438	301	07-16-2001
MPJ		05-08-2003			219	121.43	04-20-2001
FOREIGN PATENT DOCUMENTS							
Examiner Initials	Foreign Patent Document	Publication Date	Country	Name of Patentee or Applicant of Cited Document		Translation? (Yes/No/n/a)	
MPJ	EP 1 158 071 A2	28.11.2001	EUROPE	APPLIED MATERIALS, INC.		N/A	
MPJ	JP 070455542 ABSTRACT ONLY	14.02.1995	JAPAN	MATSUSHITA ELECTRIC IND CO LTD		N/A	
MPJ	JP 2000150908 ABSTRACT ONLY	30.05.2000	JAPAN	SEMICONDUCTOR ENERGY LAB CO LTD		N/A	
Examiner Initials	NON PATENT LITERATURE DOCUMENTS						
MPJ	Hu, C.-K., et al., "A process for improved Al(cu) reactive ion etching", Journal of Vacuum Science and Technology", May 1, 1989, pp. 682-685, Vol. 7, No. 3, American Institute of Physics, New York, U.S.						
Examiner's Signature: <i>Maureen G. Arancibia</i>			Date Considered: 03/30/2006				
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							

INFORMATION
DISCLOSURE
STATEMENT BY APPLICANT
Sheet 1 of 1



Application Number: 10/646,460
Filing Date: 08/22/2003
First Named Inventor: Kenneth COLLINS, et al.
Group Art Unit: 1763
Examiner Name: Maureen G. Arancibia
Attorney Docket Number: 006915/P09

U. S. PATENT DOCUMENTS

Examiner Initials	Document No	Publication Date	Name of Patentee or Applicant of Cited Document	Class	Subclass	Filing Date
MG	US-4,176,003	11-27-1979	BROWER ET AL.	430	313	02-22-1978
MG	US-4,579,618	04-01-1986	CELESTINO ET AL.	156	345	10-29-1984
MG	US-5,229,305	07-20-1993	BAKER	437	11	02-03-1992
MTC	US-5,885,358	03-23-1999	MAYDAN ET AL.	118	723	07-09-1996
MTC	US-5,958,140	09-28-1999	ARAMI ET AL.	118	725	07-26-1996
MG	US-5,897,713	04-27-1999	TOMIOKA ET AL.	118	723	09-17-1996
MG	US-6,121,161	09-19-2000	ROSSMAN ET AL.	438	783	01-19-1999
MG	US-6,180,496 B1	01-30-2001	FARRENS ET AL.	438	455	08-28-1998
MG	US-6,387,719 B1	05-14-2002	MVROS ET AL.	438	21	02-28-2001
MTC	US-6,432,260 B1	08-13-2002	MAHONEY ET AL.	156	345.35	08-07-2000
MTC	US-6,492,612 B1	12-10-2002	TAGUCHI ET AL.	219	121.43	07-13-2000
MTC	US-6,643,557 B1	11-04-2003	MILLER ET AL.	700	110	07-09-2000
MTC	US-6,645,828 B1	11-11-2003	FARRENS ET AL.	438	455	09-08-2000
MTC	US-6,780,759 B2	08-24-2004	FARRENS ET AL.	438	635	10-01-2001
MTC	US 2003/0029567 A1	02-13-2003	DHINDSA ET AL.	156	345.47	12-31-2001
MTC	US 2003/0211705 A1	11-23-2003	TONG ET AL.	438	455	06-13-2003
MTC	US 2004/0036038 A1	02-26-2004	OKUMURA ET AL.	250	492.2	07-13-2003
MTC	US 2004/0092084 A1	05-13-2004	RAYSSAC	438	455	10-30-2003
MTC	US 2004/0126993 A1	07-01-2004	CHAN ET AL.	438	455	12-30-2002

FOREIGN PATENT DOCUMENTS

Examiner Initials	Foreign Patent Document	Publication Date	Country	Name of Patentee or Applicant of Cited Document	Translation? (Yes/No/n/a)
MG	EP 1 054 433 A1	22.11.2000	EUROPE	OHIRA, KOUCHI, ET AL.	N/A
MG	JP 04318168 A ABSTRACT ONLY	11.09.1992	JAPAN	KUWABARA HAJIME	N/A
MG	JP 07130496 A ABSTRACT ONLY	19.05.1995	JAPAN	KAZUMICHI SUZUKI	N/A
MG	JP 09186337 A ABSTRACT ONLY	15.07.1997	JAPAN	NAKAHORI MASAKI	N/A

NON PATENT LITERATURE DOCUMENTS

MG	Chediak, Alex, et al., "SIMOX - The "Winner" for 300 mm SOI Wafer Fabrication", T/CS 5, April 26, 2002, pp. 1-6.

Examiner's Signature: *Maureen G. Arancibia*

Date Considered: 03/30/2006

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.